

# UNITED STATES PATENT AND TRADEMARK OFFICE

UNITED STATES DEPARTMENT OF COMMERCE United States Patent and Trademark Office Address: COMMISSIONER FOR PATENTS P.O. Box 1450 Alexandria, Virginia 22313-1450 www.uspto.gov

APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/002,933	11/01/2001	Jeong S. Lee	ACSC 60355 (2750)	5440
7590 05/05/2004		EXAMINER		
	). HANKE, ESQ. FUI	MCKANE, ELIZABETH L		
, LLP HOWARD HUGHES CENTER 6060 CENTER DRIVE, TENTH FLOOR LOS ANGLES, CA 90045			ART UNIT	PAPER NUMBER
			1744	

DATE MAILED: 05/05/2004

Please find below and/or attached an Office communication concerning this application or proceeding.

		Application No.	Applicant(s)	<i>(</i> (			
Office Action Summary		10/002,933	LEE ET AL.				
		Examiner	Art Unit				
		Leigh McKane	1744				
Period fo	The MAILING DATE of this communication app or Reply	pears on the cover sheet t	with the correspondence ac	ddress			
THE - Exte after - If the - If NC - Failt - Any	ORTENED STATUTORY PERIOD FOR REPLY MAILING DATE OF THIS COMMUNICATION. Insions of time may be available under the provisions of 37 CFR 1.1 SIX (6) MONTHS from the mailing date of this communication. It is period for reply specified above is less than thirty (30) days, a reply operiod for reply is specified above, the maximum statutory period wire to reply within the set or extended period for reply will, by statute reply received by the Office later than three months after the mailing and patent term adjustment. See 37 CFR 1.704(b).	36(a). In no event, however, may a y within the statutory minimum of the will apply and will expire SIX (6) MC , cause the application to become	a reply be timely filed  Intry (30) days will be considered time  DNTHS from the mailing date of this of ABANDONED (35 U.S.C. § 133).				
1)⊠	Responsive to communication(s) filed on 04 I	<u> March 2004</u> .					
2a)⊠	This action is <b>FINAL</b> . 2b) Th	is action is non-final.					
3)□ Disposit	Since this application is in condition for allowationsed in accordance with the practice under ion of Claims			he merits is			
-	Claim(s) 1-3,5,7-12,14-24 and 26-33 is/are pe	ending in the application					
٠/ڪ	4a) Of the above claim(s) is/are withdraw						
5)⊠	Claim(s) <u>1-3,5,7-12,21-24 and 26</u> is/are allowe						
·	Claim(s) <u>14,15 and 27-33</u> is/are rejected.						
·	Claim(s) 16-20 is/are objected to.						
	Claim(s) are subject to restriction and/o	r election réquirement					
	ion Papers	r oleotteri requirement.					
9)	The specification is objected to by the Examine	r.					
10)	The drawing(s) filed on is/are: a) accept	oted or b)□ objected to by	the Examiner.				
	Applicant may not request that any objection to the		•				
11)	The proposed drawing correction filed on	_ is: a)☐ approved b)☐	disapproved by the Examir	ner.			
	If approved, corrected drawings are required in re						
12)	The oath or declaration is objected to by the Ex	aminer.					
Priority (	under 35 U.S.C. §§ 119 and 120						
13)	Acknowledgment is made of a claim for foreign	n priority under 35 U.S.C	. § 119(a)-(d) or (f).				
a)	☐ All b)☐ Some * c)☐ None of:						
	1. Certified copies of the priority document	s have been received.					
	2. Certified copies of the priority documents have been received in Application No						
* (	3. Copies of the certified copies of the prior application from the International Buse the attached detailed Office action for a list	reau (PCT Rule 17.2(a))		l Stage			
	Acknowledgment is made of a claim for domesti			al application).			
a	) ☐ The translation of the foreign language pro Acknowledgment is made of a claim for domest	ovisional application has	been received.	,			
ر اسارت Attachmen		to priority under 00 0.0.0	2. 33 120 and/or 121.				
1) 🛛 Notic	e of References Cited (PTO-892) te of Draftsperson's Patent Drawing Review (PTO-948)		v Summary (PTO-413) Paper No f Informal Patent Application (PT				
	mation Disclosure Statement(s) (PTO-1449) Paper No(s) _	6)  Other:					

Art Unit: 1744

## Claim Rejections - 35 USC § 103

- The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all 1. obviousness rejections set forth in this Office action:
  - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 2. Claims 14, 15, and 27-30 are rejected under 35 U.S.C. 103(a) as being unpatentable over Chen et al (U.S. Patent No. 5,849,846) in view of Sun et al (U.S. Patent No. 5,728,748).

Chen et al teaches a method of sterilizing a medical device component wherein the component (e.g. dilation catheter tubing material for balloons and catheters) is irradiated with an electron beam (col.9, lines 21-45) so as to increase the burst strength, fatigue strength, and burst (i.e. rupture) pressure. \*Note: As Chen teaches that the burst pressure (i.e. rupture pressure) is increased, then the second rupture pressure is not significantly less than the first rupture pressure. Chen et al is silent as to whether the e-beam radiation sterilizes the component. However, Sun et al teaches that e-beam radiation is effective in sterilizing polymeric materials. As the component of Chen et al will have to eventually undergo sterilization before use and since it is fabricated from a polymeric material like the components of Sun et al, one of ordinary skill in the art would have found it obvious to use the e-beam sterilization of Chen et al to both improve the performance characteristics of the component and to sterilize the component.

Although Chen et al does not disclose treating the component within a sealed, evacuated container, Sun et al teaches a method of sterilizing a medical implant wherein the implant is placed within an air-tight container, the container evacuated and then repressurized with an inert

Art Unit: 1744

gas. As Sun et al discloses that removing oxygen from the environment of the implant is necessary to prevent oxidation of the implant, it would have been an obvious step in the method of Chen et al. See col.4, lines 58-65).

3. Claims 31 is rejected under 35 U.S.C. 103(a) as being unpatentable over Chen et al in view of Sun et al as applied to claim 27 above, and further in view of Avellanet (U.S. Patent No. 5,733,496).

Chen et al teaches the application of electron beam radiation to polymeric catheter balloons but does not teach balloons made of the instant materials. However, Avellanet teaches irradiating catheter balloons made of polyether block amide (PEBAX) and PTFE. See col.3, lines 10 and 17; lines 46-48. As these materials are known both to be used in catheter balloons and to be capable of being irradiated, it would have been obvious to one of ordinary skill in the art to apply the method of Chen et al with Sun et al to catheter balloons made of PEBAX or PTFE.

4. Claim 32 is rejected under 35 U.S.C. 103(a) as being unpatentable over Chen et al in view of Sun et al, Avellanet, and Lafont et al (U.S. Patent No. 5,957,975).

Chen et al teaches a method of sterilizing a medical device component wherein the component (e.g. dilation catheter tubing material for balloons and catheters) is irradiated with an electron beam (col.9, lines 21-45) so as to increase the burst strength, fatigue strength, and burst (i.e. rupture) pressure. \*Note: As Chen teaches that the burst pressure (i.e. rupture pressure) is increased, then the second rupture pressure is equal to or not significantly less than the first rupture pressure. Chen et al is silent as to whether the e-beam radiation sterilizes the component. However, Sun et al teaches that e-beam radiation is effective in sterilizing polymeric materials.

Art Unit: 1744

As the component of Chen et al will have to eventually undergo sterilization before use and since it is fabricated from a polymeric material like the components of Sun et al, one of ordinary skill in the art would have found it obvious to use the e-beam sterilization of Chen et al to both improve the performance characteristics of the component and to sterilize the component.

Although Chen et al does not disclose treating the component within a sealed, evacuated container, Sun et al teaches a method of sterilizing a medical implant wherein the implant is placed within an air-tight container, the container evacuated and then repressurized with an inert gas. As Sun et al discloses that removing oxygen from the environment of the implant is necessary to prevent oxidation of the implant, it would have been an obvious step in the method of Chen et al. See col.4, lines 58-65).

Chen et al teaches the application of electron beam radiation to polymeric catheter balloons but does not teach balloons made of the instant materials. However, Avellanet teaches irradiating catheter balloons made of polyether block amide (PEBAX) and PTFE. See col.3, lines 10 and 17; lines 46-48. As these materials are known both to be used in catheter balloons and to be capable of being irradiated, it would have been obvious to one of ordinary skill in the art to apply the method of Chen et al with Sun et al to catheter balloons made of PEBAX or PTFE.

Chen et al with Sun et al fails to disclose that the balloon catheter is a stent delivery balloon catheter. However, Lafont et al teaches a stent delivery balloon catheter comprising an elongated shaft, a balloon mounted on the shaft, wherein the entire system can be sterilized with electron beam. See col.8, lines 39-45. Therefore, it would have been obvious to employ the method of the combination to sterilize assembled stent delivery systems. As to the limitation

requiring that "sections of the balloon located directly underneath the stent are penetrated less by the electron beam than are sections of the balloon located at spaces in a wall of the stent," this is an inherent occurrence of radiation sterilization, as the balloon will be shadowed by the stent.

5. Claim 33 is rejected under 35 U.S.C. 103(a) as being unpatentable over Lafont et al in view of Sun et al.

Lafont et al teaches a method of sterilizing a balloon catheter wherein a stent is mounted on an outer surface of a balloon of a balloon catheter and the entire assembly is sterilized with electron beam radiation. See col.8, lines 39-45. Lafont et al does not disclose purging a container with the catheter therein and filling the container with an inert gas. Sun et al teaches a method of sterilizing a medical implant wherein the implant is placed within an air-tight container, the container evacuated and then repressurized with an inert gas. As Sun et al discloses that removing oxygen from the environment of the implant is necessary to prevent oxidation of the implant, it would have been an obvious step in the method of Lafont et al. As to the limitation that "the stent reduces penetration of the electron beam into sections of the balloon located directly underneath the stent," this is a necessary result of radiation sterilization.

### Allowable Subject Matter

- 6. Claims 1-12, 21-24, and 26 are allowed.
- 7. Claims 16-20 are objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.

## Response to Arguments

- Applicant's arguments filed 4 March 2004 have been fully considered but they are not 8. persuasive.
- On page 9, applicant argues that since Chen et al discloses that irradiating the catheter 9. balloon increases the burst pressure and fatigue strength of the balloon, then the method of Chen et al does not render obvious the instant claims which require that the second rupture pressure be "equal to or not significantly less than the first rupture pressure." However, if the rupture pressure is increased, as it is in the method of Chen et al, then it is "not significantly less than the first rupture pressure."
- 10. As to the combination of Chen et al with Sun et al, the motivation to combine the two references has been given in the rejection above. Applicant's arguments that the oxidative degradation avoided by Sun et al is the equivalent of the radiation-induced toughening desired by Chen et al have no foundation in the prior art of record.
- With respect to the arguments concerning Avellanet, the Examiner submits that if is 11. known to irradiate a catheter shaft made of PEBAX or PTFE, it would have been obvious to irradiate a balloon formed of the same material.

#### Conclusion

12. Applicant's amendment necessitated the new ground(s) of rejection presented in this Office action. Accordingly, THIS ACTION IS MADE FINAL. See MPEP § 706.07(a). Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

Art Unit: 1744

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the date of this final action.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Leigh McKane whose telephone number is 571-272-1275. The examiner can normally be reached on Monday-Wednesday (7:15 am-4:45 pm).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Robert J. Warden can be reached on 571-272-1275. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR

Art Unit: 1744

system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Leigh McKane

**Primary Examiner** 

Art Unit 1744

elm

3 May 2004